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(54) ANTIFOULING COATING MATERIAL COMPOSITION, ANTIFOULING COATING MEMBRANE, VESSEL OR UNDERWATER STRUCTURE COATED WITH THE ANTIFOULING COATING MEMBRANE, AND ANTIFOULING METHOD FOR VESSEL OUTER PLATE OR UNDERWATER STRUCTURE

(57)Abstract:

PROBLEM TO BE SOLVED: To obtain an antifouling coating material composition that can form an antifouling coating membrane which can retain hydrolytic properties for a long of time and is excellent

in durable antifouling properties.

SOLUTION: The objective antifouling coating material composition comprises (a) a polymerizable unsaturated carboxylate metal salt-component unit-including polymer, (b) copper and/or an inorganic copper compound, (c) a metal pyrithione and (d) at least one kind of an organic antifouling agent selected from the group consisting of a triphenylboron amine complex, a tetraphenylboron ammonium salt, tetramethylthiuram disulfide, zincdimethyldithiocarbamate, manganese 2ethylenebisdithiocarbamate, N,N- dimethyldichorophenylurea, 2,4,6-trichlorophenylmaleimide, 2methylthio-4-tert.-butylamino-6- cyclopropyl-s-triazine, 4,5-dichloro-2-n-6-octyl-4-isothiazolin-3one, 2,4,5,6- tetrachloroisophthalonitrile. Further, this invention relates to an antifouling coating membrane formed by coating the composition and curing the resulting membrane, vessels and underwater structures covered with the antifouling coating membrane and an antifouling method for the outside plates of the vessels and underwater structures.

## **LEGAL STATUS**

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